

**IN THE SPECIFICATION**

*Paragraph at page 10, line 21:*

Given the aim of photolithographic apparatus **10** as providing an optimal transmission medium path for irradiating a workpiece, e.g. a wafer, contained within pressure-tight workpiece cell **8** with a suitable photolithographic light source, cell cover **4** preferably comprises a transparent material selected for low light absorption characteristics. As shown by the cross-hatching in the drawing, the cell cover 4 is one-piece, unitary, and integral. In addition to providing the overhead boundary of workpiece cell **8**, cell cover **4** further includes an upper surface **6** and sidewall members **3** mutually configured to define an open reservoir volume vertically bounded by the upper edges of sidewall members **3** and disposed in an overlapping manner over workpiece cell **8**. As shown in the depicted embodiment, the open reservoir has a substantially planar bottom surface extending to or slightly beyond the edges of the workpiece cell **8** as defined by support members **15**. The planar bottom surface of the open reservoir is preferably bounded at its peripheral edges by an indented gutter channel **16**. It should be noted that while the depicted embodiment employs an open reservoir implementation, in the alternative, the reservoir supported by cell cover **4** may be enclosed or otherwise covered to prevent contaminants from entering an immersion fluid contained therein.